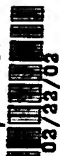


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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

063
897

APPL NUM 10080507	FILING DATE 02/22/2002	CLASS 430	SUBCLASS	GAU 1752	EXAMINER
**APPLICANTS: Jung Jae; Kong Keun; Jung Min; Lee Geun; Baik Ki;					
**CONTINUING DATA VERIFIED: THIS APPLICATION IS A CIP OF 09/465,111 12/16/1999 ABN					
** FOREIGN APPLICATIONS VERIFIED: REPUBLIC OF KOREA 98-63793 12/31/1998					
PG-PUB		DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiners's initials				ATTORNEY DOCKET NO 00939B-068710US	
TITLE : Cross-linking monomers for photoresist, and process for preparing photoresist polymers using the same					

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drwg.	Figs.Drwg. Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner Application Examiner	
<input type="checkbox"/> PREPARED FOR ISSUE		WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.	

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